

§ 413.03

Chlorodibromomethane
Hexachlorobutadiene
Hexachlorocyclopentadiene
Isophorone
Naphthalene
Nitrobenzene
2-nitrophenol
4-nitrophenol
2,4-dinitrophenol
4,6-dinitro-o-cresol
N-nitrosodimethylamine
N-nitrosodiphenylamine
N-nitrosodi-n-propylamine
Pentachlorophenol
Phenol
Bis (2-ethylhexyl) phthalate
Butyl benzyl phthalate
Di-n-butyl phthalate
Di-n-octyl phthalate
Diethyl phthalate
Dimethyl phthalate
1,2-benzanthracene
(benzo(a)anthracene)
Benzo(a)pyrene (3,4-benzopyrene)
3,4-Benzofluoranthene
(benzo(b)fluoranthene)
11,12-benzofluoranthene
(benzo(k)fluoranthene)
Chrysene
Acenaphthylene
Anthracene
1,12-benzoperylene
(benzo(ghi)perylene)
Fluorene
Phenanthrene
1,2,5,6-dibenzanthracene
(dibenzo(a,h)anthracene)
Indeno (1,2,3-cd) pyrene)
(2,3-o-phenylene pyrene)
Pyrene
Tetrachloroethylene
Toluene
Trichloroethylene
Vinyl chloride (chloroethylene)
Aldrin
Dieldrin
Chlordane (technical mixture and metabolites)
4,4-DDT
4,4-DDE (p,p-DDX)
4,4-DDD (p,p-TDE)
Alpha-endosulfan
Beta-endosulfan
Endosulfan sulfate
Endrin
Endrin aldehyde
Heptachlor
Heptachlor epoxide
(BHC-hexachlorocyclohexane)
Alpha-BHC
Beta-BHC
Gamma-BHC
Delta-BHC
(PCB-polychlorinated biphenyls)
PCB-1242 (Arochlor 1242)
PCB-1254 (Arochlor 1254)
PCB-1221 (Arochlor 1221)

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PCB-1232 (Arochlor 1232)
PCB-1248 (Arochlor 1248)
PCB-1260 (Arochlor 1260)
PCB-1016 (Arochlor 1016)

Toxaphene
2,3,7,8-tetrachlorodibenzo-
p-dioxin (TCDD)

(Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, 33 U.S.C. 1251 *et. seq.*, as amended by the Clean Water Act of 1977, Pub. L. 95–217))

[46 FR 9467, Jan. 28, 1981, as amended at 48 FR 32483, July 15, 1983; 48 FR 43681, Sept. 26, 1983; 51 FR 40421, Nov. 7, 1986]

§ 413.03 Monitoring requirements.

(a) In lieu of monitoring for TTO, the control authority may allow industrial users of POTWs to make the following certification as a comment to the periodic reports required by § 403.12(e): “Based on my inquiry of the person or persons directly responsible for managing compliance with the pretreatment standard for total toxic organics (TTO), I certify that, to the best of my knowledge and belief, no dumping of concentrated toxic organics into the wastewaters has occurred since filing the last discharge monitoring report. I further certify that this facility is implementing the toxic organic management plan submitted to the control authority.”

(b) In requesting that no monitoring be required industrial users of POTWs shall submit a toxic organic management plan that specifies to the control authority’s satisfaction the toxic organic compounds used; the method of disposal used instead of dumping, such as reclamation, contract hauling, or incineration; and procedures for assuring that toxic organics do not routinely spill or leak into the wastewater.

(c) If monitoring is necessary to measure compliance with the TTO standard the industrial user need analyze only for those pollutants which

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would reasonably be expected to be present.

(Approved by the Office of Management and Budget under control number 2040-0074)

(Secs. 301, 304, 306, 307, 308, and 501 of the Clean Water Act (the Federal Water Pollution Control Act Amendments of 1972, 33 U.S.C. 1251 *et. seq.*, as amended by the Clean Water Act of 1977, Pub. L. 95-217))

[48 FR 32483, July 15, 1983; 48 FR 43681, Sept. 26, 1983, as amended at 49 FR 34823, Sept. 4, 1984]

§ 413.04 Standards for integrated facilities.

Pretreatment standards for integrated facilities shall be computed as required by § 403.6(e) of EPA's General Pretreatment Regulations. In cases where electroplating process wastewaters are combined with regulated wastewaters which have 30 days average standards, the corresponding 30 day average standard for the electroplating wastewaters must be used. The 30 day average shall be determined for pollutants in the relevant subcategory from the corresponding daily and 4 day average values listed in the table below.

If the maximum for any 1 day is	And the 4 day average is	Then the 30 day average is
0.6	0.4	0.3
1.27	.5
1.9	1	.55
4.1	2.6	1.8
4.2	2.6	1.8
4.5	2.7	1.8
5.0	2.7	1.5
7.0	4	2.5
10.5	6.8	5
20.0	13.4	10
23	16	12
47	29	20
53	36	27
74	39	21
107	65	45
169	89	49
160	100	70
164	102	70
176	105	70
273	156	98
365	229	160
374	232	160
401	241	160
410	267	195
623	257	223
935	609	445

Subpart A—Electroplating of Common Metals Subcategory

§ 413.10 Applicability: Description of the electroplating of common metals subcategory.

The provisions of this subpart apply to dischargers of pollutants in process wastewaters resulting from the process in which a ferrous or nonferrous basis material is electroplated with copper, nickel, chromium, zinc, tin, lead, cadmium, iron, aluminum, or any combination thereof.

§ 413.11 Specialized definitions.

For the purpose of this subpart:

(a) The term *sq m* [“sq ft”] shall mean the area plated expressed in square meters [square feet].

(b) The term *operation* shall mean any step in the electroplating process in which a metal is electrodeposited on a basis material and which is followed by a rinse; this includes the related operations of alkaline cleaning, acid pickle, stripping, and coloring when each operation is followed by a rinse.

§§ 413.12–413.13 [Reserved]

§ 413.14 Pretreatment standards for existing sources.

Except as provided in §§ 403.7 and 403.13 of this title, any existing source subject to this subpart which introduces pollutants into a publicly owned treatment works must comply with 40 CFR part 403 and achieve the following pretreatment standards for existing sources (PSES):

(a) No user introducing wastewater pollutants into a publicly owned treatment works under the provisions of this subpart shall augment the use of process wastewater or otherwise dilute the wastewater as a partial or total substitute for adequate treatment to achieve compliance with this standard.

(b) For a source discharging less than 38,000 liters (10,000 gal.) per calendar day of electroplating process wastewater the following limitations shall apply: